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10/07/6630  
02/19/02

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PATENT NUMBER and  
ISSUE DATE

## U.S. UTILITY Patent Application

912

APPL NUM 10076630	FILING DATE 02/19/2002	CLASS 438	SUBCLASS	GAU 2812	EXAMINER
**APPLICANTS: Chung Chia-Chi; Hsueh Chen-Chen;					
**CONTINUING DATA VERIFIED:					
** FOREIGN APPLICATIONS VERIFIED:					
PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>			
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiners's initials		<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO 8409.0004-00		
TITLE : Self-aligned patterning in dual damascene process					
U.S.DEP'T. OF COMM./PAT. & TM-PTO-438L(Rev. 12-94)					

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED			
Amount Due	Date Paid		Total Claims	Print Claim for O.G.		
				DRAWING		
				Sheets Drwg. 2	Figs.Drwg. 6	Print Fig. 3,4,5
TERMINAL DISCLAIMER		Primary Examiner	Application Examiner			
		PREPARED FOR ISSUE				
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